

UVC Standards — Physical and Documentary

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Discharge Lamps



Low pressure mercury Medium pressure mercury Xenon and pulsed xenon Excimer lamps

Method for the Measurement of the **Output of Monochromatic (254 nm)** Low-Pressure UV Lamps*

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Approved Method Total Flux Measurement of Lamps Using an **Integrating Sphere**

> LM-75-19 – IES Guide to Goniometer Measurements, Types, and **Photometric Coordinate Systems**

IES LM-9-09/R17

Approved Method: Electrical and

Photometric Measurement of Fluorescent Lamps

Measurement quantities:

Total radiant flux (W) or (W/nm)

Radiant intensity distribution (W/sr)

Electrical power (W)

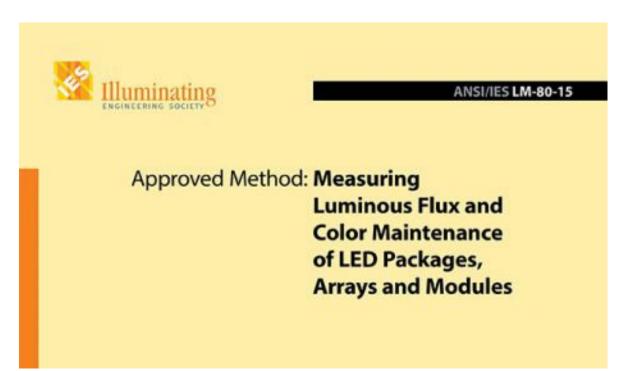


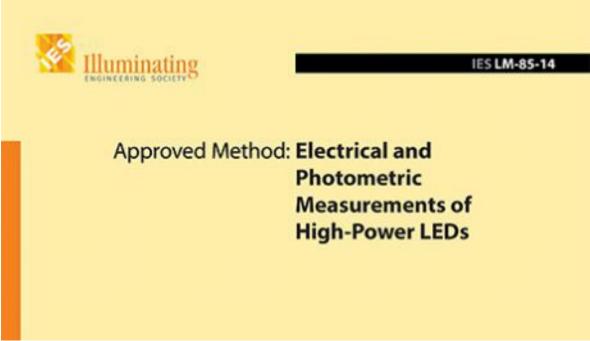
LED Chips and Arrays



Leverage existing standards

Extension of existing infrastructure





Electrical and Optical Radiant power maintenance

Complete UV Devices



Leverage existing standards
Extension of existing infrastructure















UV Device Irradiance











IES/TPC Project C303-16 - Application Distance Radiometry

This document describes the method for measuring illuminance, irradiance, and/or photon irradiance (i.e., photon flux density) at multiple points on a plane at a specific application distance.



Physical Standards from NIST





Wavelength (nm)	Expanded Uncertainty (k=2) %
200	1.07
250	0.95
300	0.97
350	0.99
400	1.04

Expanded Uncertainty (k=2) %
1.74
1.27
0.91
0.77
0.57





Wavelength (nm)	Expanded Uncertainty (k=2) %
200	4.7
250	1.8
300	1.0
350	0.82
400	0.60





UVC Chip & Array Calibration Facility

LGS350-110 benchtop version





Measurements of High-Power LEDs"

UVC Source Measurement Facility

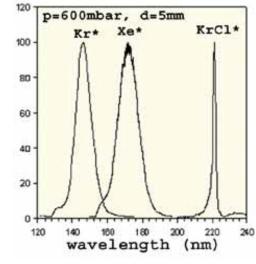




1.5 m sphere system coated with a PTFE film intended for UV water reactors

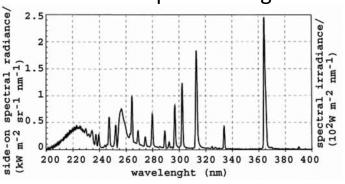
Spectroradiometer detection

Sources and small products



Low pressure Hg

Medium pressure Hg



ArF*, KrCl*, KrF*, XeBr*, XeCl*, XeF*, emit at 193, 222, 248, 282, 308, 351 nm

NIST Research Comparing Methods



Keitz Formula (1971)

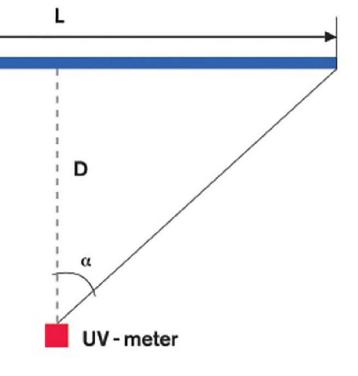
$$P = \frac{E2\pi^2 DL}{2\alpha + \sin 2\alpha}$$



D is distance (m) from lamp center to the UV sensor.

L is the lamp arc length (m) from electrode tip to electrode tip.

 α is the half angle (radians) subtended by the lamp at the sensor position. That is, $\tan \alpha = L/(2D)$



UVC Detector Measurement Facility

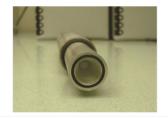




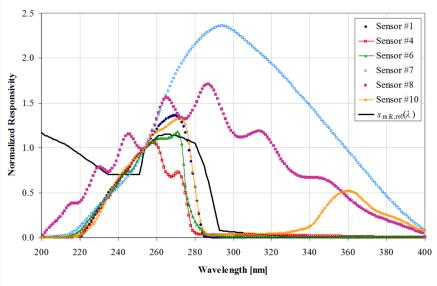


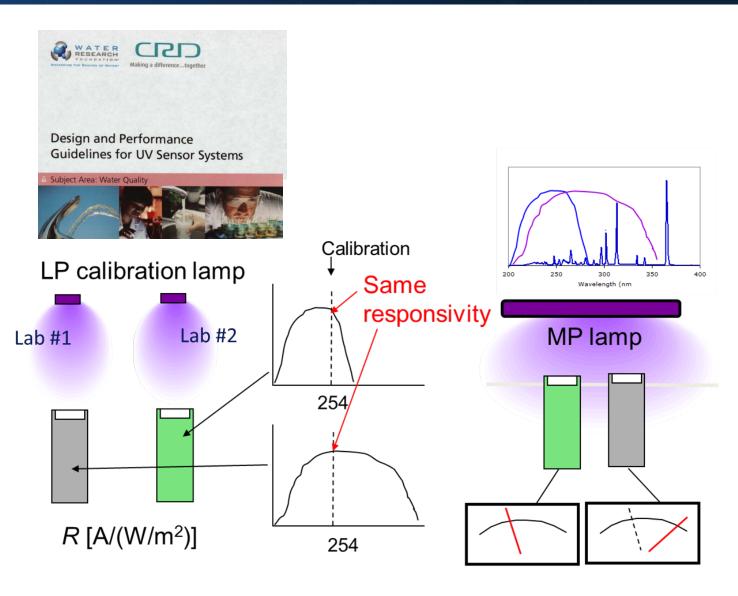












NIST Accreditation & Proficiency Testing



Leverage previous experience

- National Voluntary Laboratory Accreditation Program (NVLAP)

> **NIST Measurement** Assurance Program (MAP)

NVLAP Energy Efficient Lighting Products

NIST Handbook 150-1-2019

National Voluntary Laboratory Accreditation Program Standards Coordination Office Laboratory Programs

Standards Services

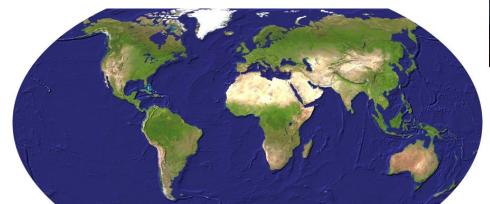
This publication is available free of charge from: https://doi.org/10.6028/NIST.HB.150-1-2019

February 2019



MAP 1: 118 Laboratories worldwide Jan 2010 – Dec 2014

MAP 2: 128 Laboratories worldwide Jan 2015 – Dec 2020





Summary



Memorandum of Understanding

International Ultraviolet Association (IUVA)

Illuminating Engineering Society (IES)

Four documentary standard topics

Total radiant flux and radiant intensity distribution measurement of discharge sources;

Total radiant flux and radiant intensity distribution measurement of LED chips and arrays;

Total radiant flux and radiant intensity distribution of complete UV devices; and

Application distance radiometry of UVC devices

NIST continues to improve infrastructure to support documentary standard development